M.Tech. 2nd Semester (ECE) CBCS Examination,

May-2017

VLSI DESIGN

Paper-MTECE22D4

Time allowed: 3 hours] [Maximum marks: 100 Note: Q. No. 1 is compulsory. Attempt any one question from each section. Explain the following: Body Effect. **CMOS** Design Rules (b) Thermal Aspect of Processing in the MOS Technology. Architectural issues in VLSI. 5 Section-A What is the meaning of depletion in MOSFET? Discuss in brief the theory of depletion type MOSFET with suitable diagrams used. 10 What is the difference between N-MOS and P-MOS? Which one is preferred over the other? Explain in detail. 10 **22670**—P-3-Q-9 (17) P.T.O.

(2)		

3.	What do you mean by fabrication process? Explain in				
	brief the CMOS fabrication process using Twin-Tub				
	process in detail. 20				

Section-B

- 4. In the inverter circuit, what is meant by $Z_{P,U}$, and $Z_{P,d}$?

 Derive the required ratio between $Z_{P,U}$, and $Z_{P,d}$ if an n-MOS inverter is to be driven from another n-MOS inverter.
- 5. (a) What do you mean by Latch-up problem in CMOS circuit? How can it be avoided? Explain. 10
 - (b) Explain the operation of Pass transistor? Can it be used as an AND Gate? Explain.

Section-C

- 6. (a) What is the meaning of Stick Diagram? Why it is used? What are the different rules for designing a stick diagram? Explain.
 - (b) What do you mean by the following:
 - (i) Delay unit and inverter delay.

	(ii) Propagation Delay.	10			
7.	Draw stick diagram of the given equation:				
	(i) Y=A+B+CD	7			
	(ii) 2-input XOR Gate	7			
	(iii) CMOS Buffer.	6			
	Section-D				
8.	What is the meaning of Scaling of MOS transistors? What are the different factors used in scaling? Explain.				
	Also discuss about the limitations of the scaling	g. 20			
9.	Explain the following:				
	(i) Design of ALU Subsystem	6			
	(ii) FSM	· 7			
	(iii) PLA.	7			